

Design and Fabrication of High Precision Masks for TPF Coronagraph

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Exo-Planet Science & Technology Fair

Jet Propulsion Lab

Feb 22, 2008



Terrestrial Planet Finder

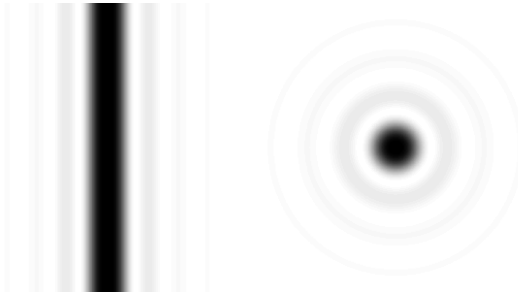
TPF

Objectives

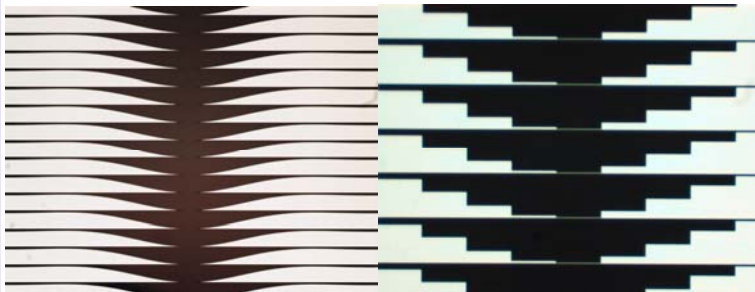
- Technology Development and Maturation
 - High Energy e-beam Writing
 - Patterning and Microlithography
 - Deep Reactive Ion Etching
 - Profiled Deposition
- Design, Fabricate, Characterize and Test various masks
 - Image Plane Masks
 - Shaped Pupil Masks
 - Vortex Masks
- Demonstrate performance in laboratory test beds
 - HCIT Tests



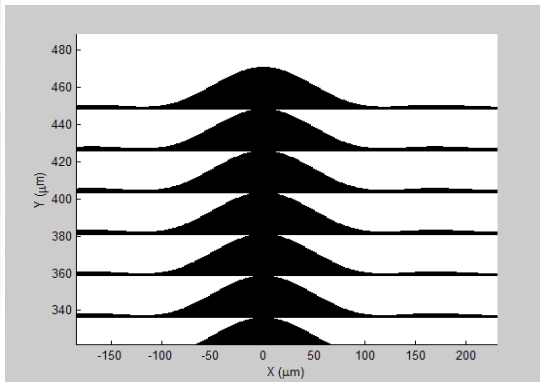
Gray Scale and Binary “Band-limited” Masks



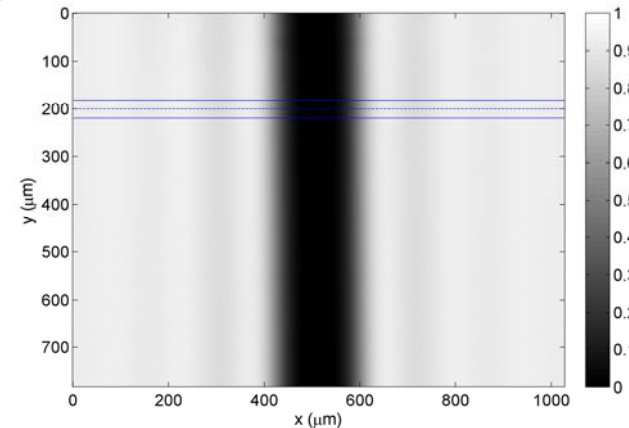
Conceptual transmission images of the inner region of (a) one- and (b) two-dimensional gray scale 1-sinc² type “band-limited” masks



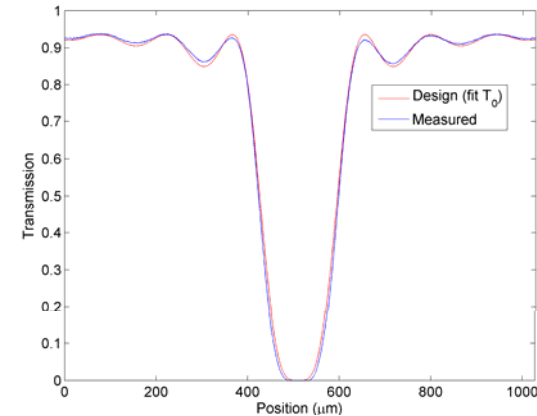
Examples of continuous binary mask and sampled binary mask fabricated and tested at JPL



Close-up view of one dimensional binary 1-sinc² type mask pattern; black areas are made of perfectly opaque and etched metal layer



Measured intensity-transmission image of a 1-sinc² type one-dimensional gray scale mask fabricated on HEBS glass at JPL. Lines indicate the region of profile averaging for cross-section data shown in figure below.



Cross-section profile of 1-sinc² mask (50-row average between lines in top figure). A fit of the design function $T(x) = T_0[1 - \text{sinc}^2(x/w)]^2$ with maximum transmittance $T_0 = 0.935$ as a parameter is shown for comparison

Shaped Pupil Masks

Princeton Designs

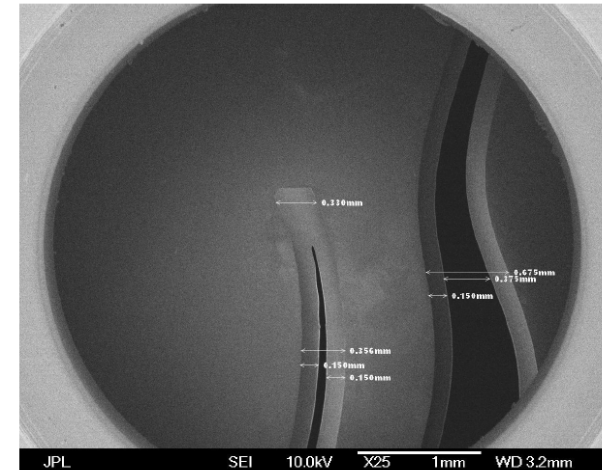
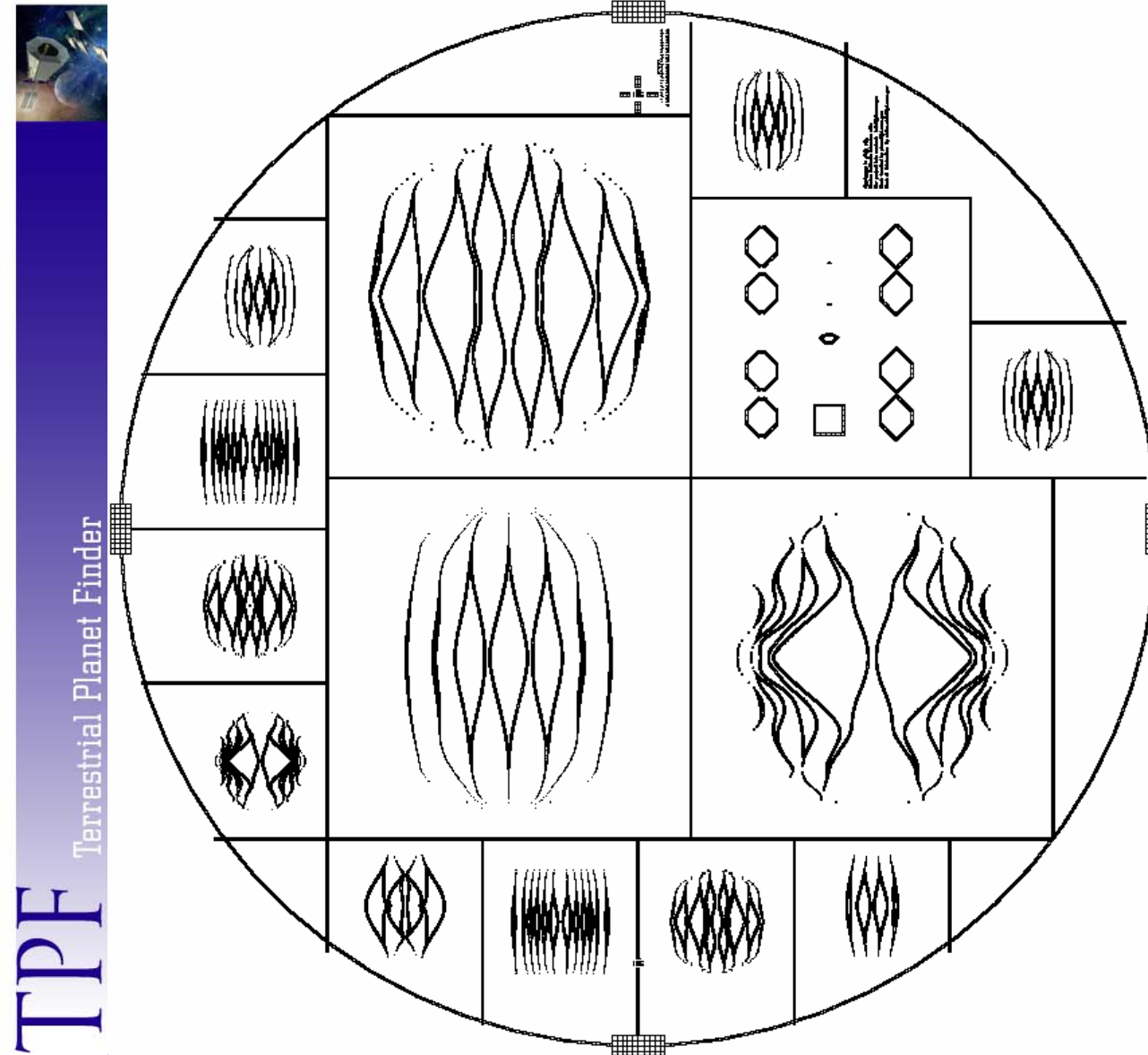


Figure 4. Typical shape and image of apertures of an actual mask fabricated by DRIE technique

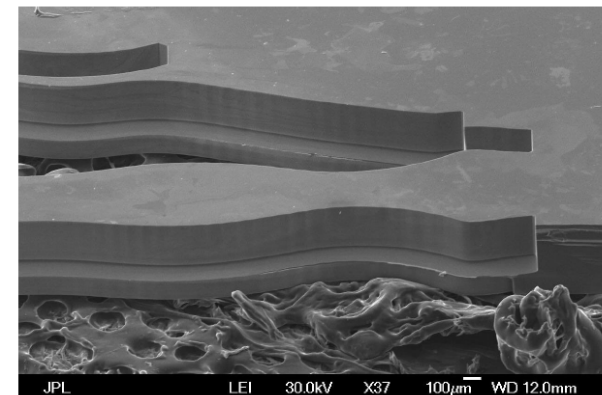
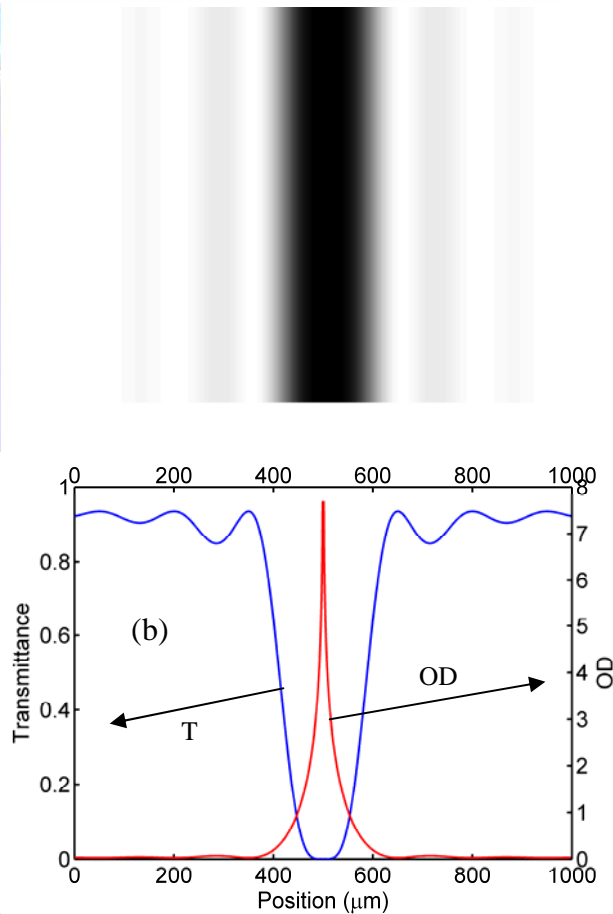


Figure 5. A mask slit seen under SEM showing recessed steps surrounding the slits

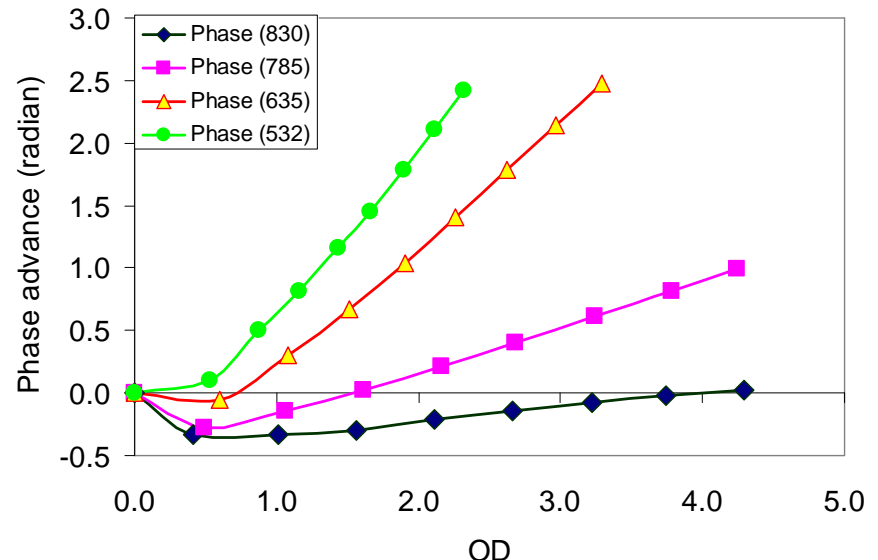
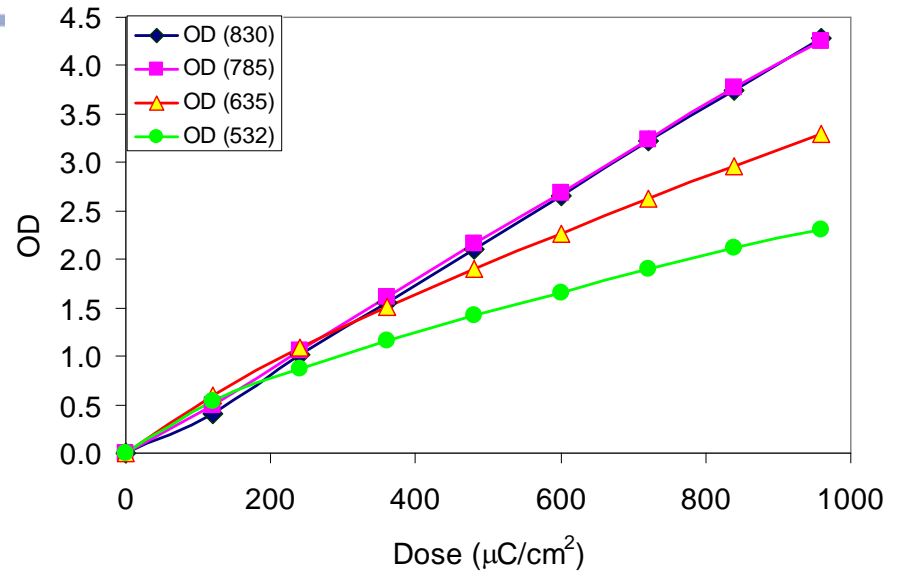
Proc. of SPIE Vol. 6265 62653N-4

HEBS Glass Image Plane Masks



A typical 1-dimensional gray scale mask transmission image (a) and cross-section transmittance and OD profiles (b).

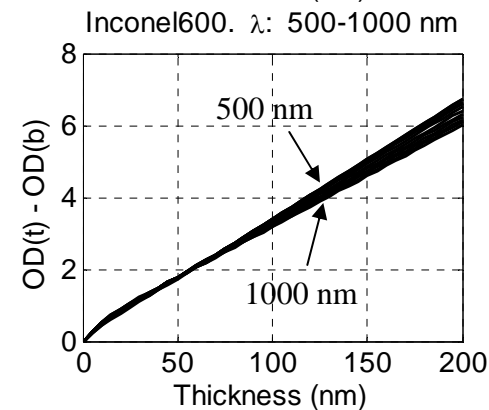
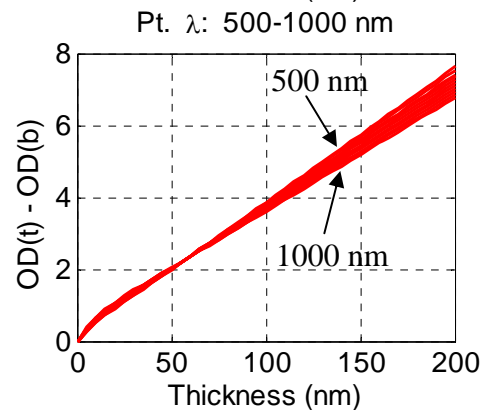
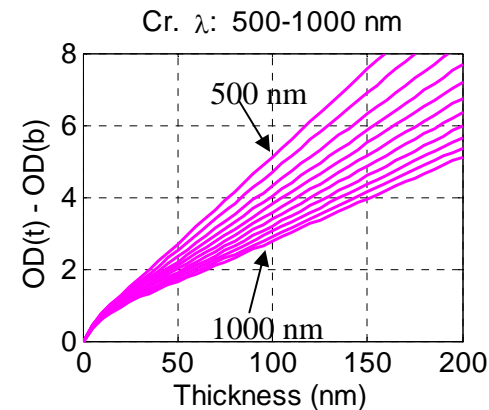
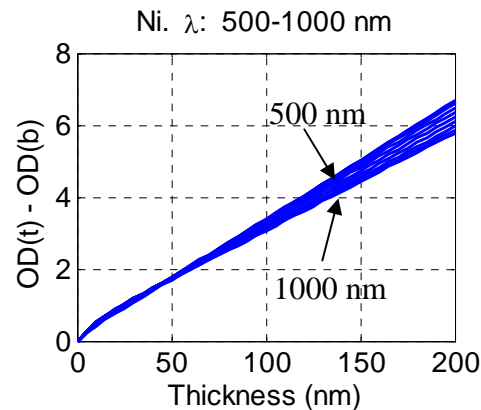
Such masks are fabricated with electron beam writing technique at JPL



Measured optical density (OD) and phase of a HEBS glass material which shows a large variation with wavelength

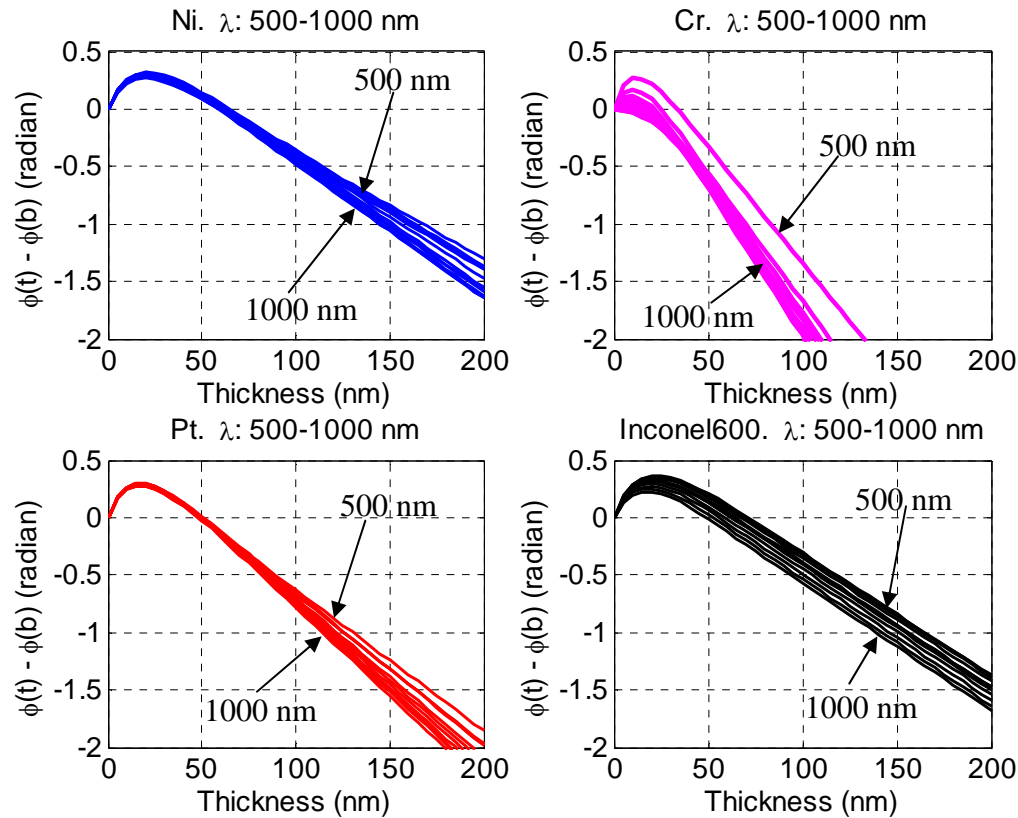
Alternative Mask Materials

Candidate Materials for Profiled Metallic Masks Low Dispersion Ni, Pt and Inconel vs. High Dispersion Cr



Appl. Optics, Jan (2008), pp. 116-125

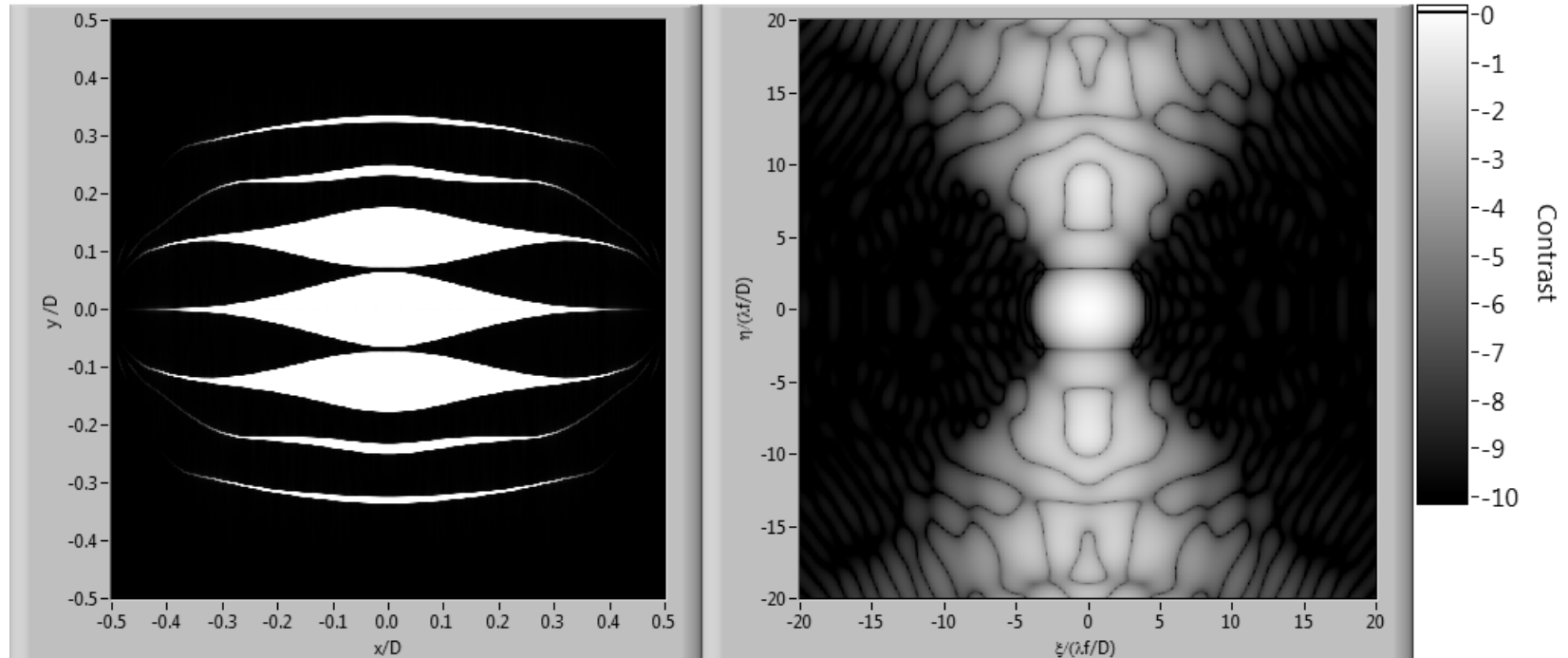
Phase Dispersion



Appl. Optics, Jan (2008), pp. 116-125

Ripple3 Shaped Pupil Mask and PSF

High Contrast Dark Zones



Shaped Pupil Mask fabricated at JPL employing Deep Reactive Ion Etching Technique PSF and dark zones obtained with this mask

Ref: Belikov et al., SPIE 6693-36 (2007)

Key Results

- Image plane masks employing High Energy Beam Sensitive (HEBS) glass have been fabricated successfully at JPL.
- With HEBS image masks, coronagraph contrast of $\sim 2.5 \times 10^{-10}$ has been demonstrated with monochromatic light in the JPL High Contrast Imaging Testbed (HCIT).
- More recently, $\sim 2 \times 10^{-9}$ contrast has been achieved in 10% broadband light with a metallic mask.
- Also, free-standing shaped pupil masks designed by Princeton University have been fabricated successfully at JPL; a record contrast of 2.4×10^{-9} with 10% broadband light has been demonstrated (Belikov et al) with such a shaped pupil mask.



Summary

- Significant advancements have been accomplished in the design and fabrication of masks
- Further work in progress to develop better masks for broadband performance

Publications

- **K. Balasubramanian, Band limited image plane masks for Terrestrial Planet Finder Coronagraph: materials and designs for broadband performance, Appl. Optics, Jan (2008), pp. 116-125**
- **K. Balasubramanian, E. Sidick, D.W. Wilson, D. J. Hoppe, S. B. Shaklan, J. T. Trauger., “Band-limited masks for TPF coronagraph”, C.R. Physique, 8, (2007), 288-297, doi:10.1016/j.crhy.2007.03.001**
- **K. Balasubramanian, D. J. Hoppe, P. G. Halverson, D. W. Wilson, P. M. Echternach, F. Shi, A. E. Lowman, A. F. Niessner, J. T. Trauger, and S. B. Shaklan., “Occulting Focal Plane Masks for Terrestrial Planet Finder Coronagraph – Design, Fabrication, Simulations and Test Results”, Proc. of IAU Colloquium 200, Direct Imaging of Exo-Planets, Cambridge University Press, (2006) pp. 405-409.**
- **Ruslan Belikov, Amir Give'on, Brian Kern, Eric Cady, Michael Carr, Stuart Shaklan, Kunjithapatham Balasubramanian, Victor White, Pierre Echternach, Matt Dickie, John Trauger, Andreas Kuhnert, N. Jeremy Kasdin, Demonstration of High Contrast in 10% Broadband Light with the Shaped Pupil Coronagraph, Proc. SPIE 6693-36 (2007)**





Acknowledgements

This work was performed at the Jet Propulsion Laboratory, California Institute of Technology, under a contract with the National Aeronautics and Space Administration.

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Thanks to Stuart Shaklan, Daniel Hoppe, Pierre Echternach, Matthew Dickie, Wesley Traub, John Trauger, Marie Levine, Andreas Kuhnert (JPL) and Jeremy Kasdin (Princeton Univ.)